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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/748,851	12/31/2003	Vadim Yevgenyevich Banine	081468-0307473	2813
909	7590 06/14/2005		INER	
	Y WINTHROP SHAW	RUTLEDGE, DELLA J		
P.O. BOX 10500 MCLEAN, VA 22102			ART UNIT	PAPER NUMBER
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			DATE MAILED: 06/14/200	5

Please find below and/or attached an Office communication concerning this application or proceeding.

		I Amplicant/a)			
	Application No.	Applicant(s)			
	10/748,851	BANINE ET AL.			
Office Action Summary	Examiner	Art Unit			
	D. Rutledge	2851			
The MAILING DATE of this communication app Period for Reply	ears on the cover sheet with the C	orrespondence address			
A SHORTENED STATUTORY PERIOD FOR REPL' THE MAILING DATE OF THIS COMMUNICATION.  - Extensions of time may be available under the provisions of 37 CFR 1.13 after SIX (6) MONTHS from the mailing date of this communication.  - If the period for reply specified above is less than thirty (30) days, a reply if NO period for reply is specified above, the maximum statutory period was preply received by the Office later than three months after the mailing earned patent term adjustment. See 37 CFR 1.704(b).	36(a). In no event, however, may a reply be ting within the statutory minimum of thirty (30) day will apply and will expire SIX (6) MONTHS from a cause the application to become ABANDONE	nely filed s will be considered timely. the mailing date of this communication. D (35 U.S.C. § 133).			
Status					
1) Responsive to communication(s) filed on  2a) This action is FINAL. 2b) This action is non-final.  3) Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under Ex parte Quayle, 1935 C.D. 11, 453 O.G. 213.					
Disposition of Claims					
4) ☐ Claim(s) 1-41 is/are pending in the application. 4a) Of the above claim(s) is/are withdraw 5) ☐ Claim(s) is/are allowed. 6) ☐ Claim(s) 1-41 is/are rejected. 7) ☐ Claim(s) is/are objected to. 8) ☐ Claim(s) are subject to restriction and/or	vn from consideration.				
Application Papers					
9) The specification is objected to by the Examine 10) The drawing(s) filed on is/are: a) access applicant may not request that any objection to the Replacement drawing sheet(s) including the correction of the original transfer of the original transfer of the second or declaration is objected to by the Examine.	epted or b) objected to by the I drawing(s) be held in abeyance. See ion is required if the drawing(s) is ob	e 37 CFR 1.85(a). jected to. See 37 CFR 1.121(d).			
Priority under 35 U.S.C. § 119					
12) Acknowledgment is made of a claim for foreign     a) All b) Some * c) None of:     1. Certified copies of the priority documents     2. Certified copies of the priority documents     3. Copies of the certified copies of the priority application from the International Bureau * See the attached detailed Office action for a list of the certified copies.	s have been received. s have been received in Applicati ity documents have been receive ı (PCT Rule 17.2(a)).	on No ed in this National Stage			
Attachment(s)	4) ☐ Interview Summary	(PTO-413)			
Notice of Netral Pro-092) Notice of Draftsperson's Patent Drawing Review (PTO-948) Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08) Paper No(s)/Mail Date	Paper No(s)/Mail Da				

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#### **DETAILED ACTION**

## **Declaration and Power of Attorney**

1. An executed Declaration and Power of Attorney was received on 01 July 2004.

## Claim Rejections - 35 USC § 102

2. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

- (b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.
- (e) the invention was described in (1) an application for patent, published under section 122(b), by another filed in the United States before the invention by the applicant for patent or (2) a patent granted on an application for patent by another filed in the United States before the invention by the applicant for patent, except that an international application filed under the treaty defined in section 351(a) shall have the effects for purposes of this subsection of an application filed in the United States only if the international application designated the United States and was published under Article 21(2) of such treaty in the English language.
- 3. Claim 1 is rejected under 35 U.S.C. 102(b) as being anticipated by Riordan et al. (US Pat. No. 4,837,794).

Riordan et al. discloses a lithographic apparatus comprising an x-ray generating system 22 having a plasma x-ray source 24. Since the apparatus is a lithographic system the structures for patterning and for the substrate are inherent. The apparatus has a magnetic system 38 having magnets 66. The debris migration system applies a magnetic field so that at least the charged particles are mitigated.

4. Claims 1 – 41 are rejected under 35 U.S.C. 102(e) as being anticipated by Ruzic et al. (US Pat. No. 2005/0016679).

The patentees have a lithographic apparatus 105 which would inherently have the structures for the patterning means and substrate. In Fig. 3 and paragraph 18, 19, the

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reference discloses applying a magnetic field by means of coils 225, 300 and mitigating the particles toward the foil trap 305 which has a plurality of trapping surfaces. The apparatus has a source of extreme ultraviolet radiation (EUV). – claims 1-3, 5, 11 - 13, 20 - 22, 29-31, 38, 39, 41.

Paragraphs 14 -17 discloses that a radio frequency power supply, a helicon or capacitive plate system, using pulsed plasma source. A pressure gradient may be established on either side of the foil trap.

Paragraphs 18, 22 states a DC bias may be used to generate a spiral path for the particles to make them more likely to strike the trap. The foil trap may be operated in a DC or RF potential to help draw the particle toward the trap. From Fig. 3, coils 225 has a larger diameter than coil 300, such that the two coils are coaxially aligned and the particles are deflected as claimed – claim 4 - 10, 14 - 19, 23 - 28, 32-37.40

#### Response Data

Any inquiry concerning this communication or earlier communications from the examiner should be directed to D. Rutledge whose telephone number is (571) 272-2127. The examiner can normally be reached on Mon - Thurs, 6:00 AM - 4:30 PM.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Judy Nguyen can be reached on (571) 272-2258. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

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Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

D. Rutledge
Primary Examiner
Art Unit 2851

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